



(51) International Patent Classification:  
**H05G 2/00** (2006.01)

(21) International Application Number:  
PCT/NL2009/050132

(22) International Filing Date:  
20 March 2009 (20.03.2009)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:  
61/064,720 21 March 2008 (21.03.2008) US

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(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

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(54) Title: A TARGET MATERIAL, A SOURCE, AN EUV LITHOGRAPHIC APPARATUS AND A DEVICE MANUFACTURING METHOD USING THE SAME

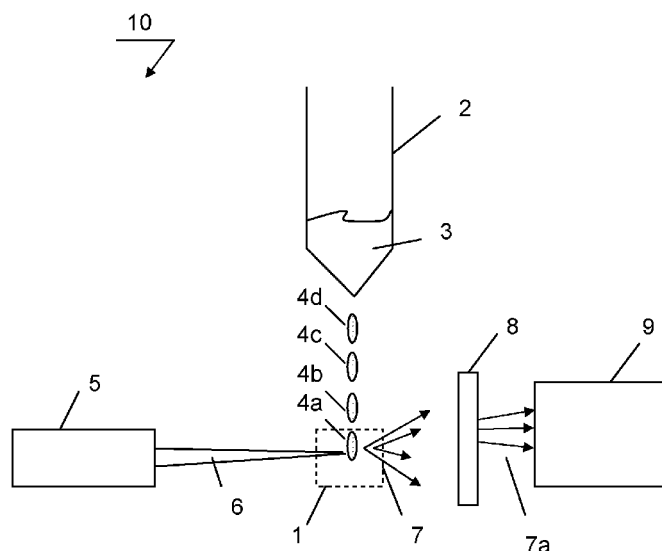


Fig. 2

(57) Abstract: A target material is configured to be used in a source constructed and arranged to generate a radiation beam having a wavelength in a 6.8 nm range. The target material includes a Gd-based composition configured to modify a melting temperature of Gd, or Tb, or a Tb-based composition configured to reduce a melting temperature of Tb.



**(84) Designated States** (*unless otherwise indicated, for every kind of regional protection available*): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

**Published:**

- with international search report (*Art. 21(3)*)
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (*Rule 48.2(h)*)

**(88) Date of publication of the international search report:**

12 November 2009